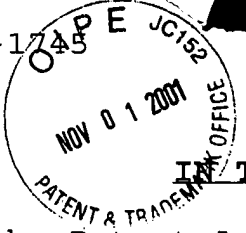


#9

SON-1745

PATENT APPLICATION



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In the Patent Application of

Seiichi FUKUDA

Serial No. 09/512,336

Filed: February 24, 2000

For: DRY ETCHING METHOD AND
METHOD OF MANUFACTURING
SEMICONDUCTOR APPARATUS

Group Art Unit: 1765

Examiner: K. Chen

PETITION TO EXTEND TIME FOR RESPONSE
TO WITHIN THE SECOND EXTENDED MONTH

Commissioner for Patents
Washington, D.C. 20231

Sir:

The applicant, through its attorneys, hereby petitions to extend time for response to the Final Official Action of June 21, 2001 to within the second extended month. The Commissioner is authorized to charge \$400.00 to Deposit Account 18-0013 to cover the petition fee for a large entity.

The Commissioner is hereby authorized to charge any additional fees associated with this communication or credit any overpayment to Deposit Account No. 18-0013. A duplicate copy of this letter is enclosed for that purpose.

Respectfully submitted,

Ronald P. Kananen
Registration No. 24,104

DATE: November 1, 2001

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